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## **Amendments to Claims**

- 1. (Currently amended) A fluorine-containing copolymer comprising; comprising:
  - (a.) a first repeat unit derived from an ethylenically unsaturated compound containing a functional group having the structure:

 $-X_f(CH_2)_qC(R_f)(R_f)OH$ 

wherein

 $R_f$  and  $R_f$  are the same or different  $C_1$ - $C_{10}$  fluoroalkyl groups, or taken together are  $(CF_2)_n$ ;

n is an integer from 2 to 10;

X is S, O, N, or P;

q = 0 and r = 0, or q = 1 and r = 0 or 1; and

(b.) a second repeat unit derived from an acrylate selected from the group consisting of CH<sub>2</sub>=CRCO<sub>2</sub>R"-and CH<sub>2</sub>=C(CH<sub>2</sub>OH)CO<sub>2</sub>R", wherein

R is H; F, or a C<sub>1</sub>-C<sub>5</sub> alkyl or fluoroalkyl group; and

R" is a polycyclic C<sub>5</sub>-C<sub>50</sub> alkyl group containing at least one hydroxyl group, group; and

R" is a C1-C25 alkyl group.

- 2. (Canceled)
- 3. (Original) The fluorine-containing copolymer of Claim 1, wherein (b) is hydroxyadamantyl acrylate.
- 4. (Original) The fluorine-containing copolymer of Claim 3, wherein the polymer further comprises a repeat unit derived from 2-methyl-2-adamantyl acrylate.
- 5. (Original) The fluorine-containing copolymer of Claim 4 made by a semibatch synthesis.
- 6. (Original) The fluorine-containing copolymer of Claim 1, further comprising a repeat unit derived from a fluoroolefin selected from the group of ethylenically unsaturated compounds containing at least one fluorine atom covalently attached to an ethylenically unsaturated carbon atom.
- 7. (Original) The fluorine-containing copolymer of Claim 6, wherein the fluoroolefin is selected from the group consisting of tetrafluoroethylene,

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chlorotrifluoroethylene, hexafluoropropylene, trifluoroethylene, and R<sub>f</sub>OCF=CF<sub>2</sub> wherein R<sub>f</sub> is a saturated fluoroalkyl group of from 1 to 10 carbon atoms.

- 8. (Original) The fluorine-containing copolymer of Claim 1, wherein r=0 and q=0.
- 9. (Original) The fluorine-containing copolymer of Claim 1, wherein q=1 and r=0.
- 10. (Original) The fluorine-containing copolymer of Claim1, wherein q=1 and r=1 and X is S, O, N or P.
- 11. (Original) The fluorine-containing copolymer of Claim 1, further comprising a repeat unit derived from at least one ethylenically unsaturated compound containing a functional group having the structure

## -C(Rf)(Rf')ORa

wherein  $R_f$  and  $R_f$  are the same or different fluoroalkyl groups of from 1 to 10 carbon atoms or taken together are  $(CF_2)_n$  wherein n is 2 to 10 and  $R_a$  is an acid- or baselabile protecting group.

- 12. (Original) The fluorine-containing copolymer of Claim 11, wherein  $R_a$  is  $CH_2OCH_2R_{15}$ , and  $R_{15}$  is hydrogen, a linear  $C_1$ - $C_{10}$  alkyl, or a branched  $C_3$ - $C_{10}$  alkyl group.
- 13. (Original) The fluorine-containing copolymer of Claim 1, wherein the functional group of repeat unit (a) is –C(CF<sub>3</sub>)<sub>2</sub>OH.
- 14. (Original) The fluorine-containing copolymer of Claim 6, wherein at least one repeat unit is cyclic or polycyclic.
- 15. (Original) The fluorine-containing copolymer of Claim 6, further comprising a repeat unit derived from a cyclic or polycyclic unsaturated compound, selected from the group of compounds represented by structures (H) or (I),

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$$R^3$$
 $R^7$ 
 $R^7$ 
 $R^8$ 
 $R^8$ 

wherein:

n is 0, 1 or 2;

a and b are independently 1, 2 or 3, except that a is not 1 when b is 2 or vice versa; and

R1 to R8 and R11 to R14 are the same or different, and each represents a hydrogen atom, a halogen atom, a carboxyl group, a C3 to C14 secondary or tertiary alkyl carboxylate, a hydrocarbon group or a substituted hydrocarbon group.

16. (Original) The fluorine-containing copolymer of Claim 15, wherein the cyclic or polycyclic unsaturated compound is selected from the group consisting of:

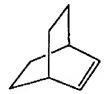
(norbonnene), 
$$CO_2C(CH_3)_3$$
,  $CO_2C(CH_3)_3$ 

16. 17. (Currently amended) The fluorine-containing copolymer of Claim 15, wherein the cyclic or polycyclic unsaturated compound is selected from the group consisting of:

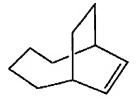
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(bicyclo[2.2.2]oct-2-ene),



- 18. (Original) The fluorine-containing copolymer of Claim 7, wherein the fluoroolefin is tetrafluoroethylene.
  - 19. (Currently amended) A photoresist comprising:
    - (a) a fluorine-containing copolymer comprising:
      - (i) a first repeat unit derived from an ethylenically unsaturated compound containing a functional group having the structure:

$$-X_f(CH_2)_qC(R_f)(R_f')OH$$

wherein

 $R_f$  and  $R_f'$  are the same or different C<sub>1</sub>-C<sub>10</sub> fluoroalkyl groups, or taken together are (CF<sub>2</sub>)<sub>n</sub>;

n is an integer from 2 to 10;

X is \$, O, N, or P;

q = 0 and r = 0, or q = 1 and r = 0 or 1; and

(ii) a second repeat unit derived from an acrylate-selected from the group-consisting of CH<sub>2</sub>=CRCO<sub>2</sub>R"-and CH<sub>2</sub>=C(CH<sub>2</sub>OH)CO<sub>2</sub>R",

wherein

R is H, F, or a C<sub>1</sub>-C<sub>5</sub> alkyl or fluoroalkyl group; and

R" is a polycyclic C<sub>5</sub>-C<sub>50</sub> alkyl group containing at least one hydroxy group; and

- -R" is a C1-C25-alkyl group; and
  - (b) at least one photoactive component.
- 20. (Original) The photoresist of Claim 19, further comprising a dissolution inhibitor.
  - 21. (Original) The photoresist of Claim 19, further comprising a solvent.

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- 22. (Currently amended) A process for preparing a photoresist image on a substrate comprising, in order:
  - (1) applying a coatable photoresist composition on a substrate, wherein the coatable photoresist composition comprises:
    - (a) a fluorine-containing copolymer comprising:
    - (i) a first repeat unit derived from an ethylenically unsaturated compound containing a functional group having the structure:

$$-X_r(CH_2)_qC(R_f)(R_f')OH$$

wherein

 $R_f$  and  $R_f$  are the same or different  $C_1$ - $C_{10}$  fluoroalkyl groups, or taken together are  $(CF_2)_n$ ;

n is an integer from 2 to 10;

X is S, O, N, or P;

q = 0 and r = 0, or q = 1 and r = 0 or 1; and

(ii) a second repeat unit derived from an acrylate selected from the group consisting of CH<sub>2</sub>=CRCO<sub>2</sub>R"-and CH<sub>2</sub>=C(CH<sub>2</sub>OH)CO<sub>2</sub>R'".

wherein

R is H, F, or a C<sub>1</sub>-C<sub>5</sub> alkyl or fluoroalkyl group;

R" is a polycyclic C<sub>5</sub>-C<sub>50</sub> alkyl group containing at least one hydroxy group; and

R" is a C1-C25-alkyl group; and

- (b) a photoactive component;
- (c) a solvent; and
- (2) drying the coatable photoresist composition to substantially remove the solvent to form a photoresist layer on the substrate;
- imagewise exposing the photoresist layer to form imaged and nonimaged areas; and
- (4) developing the exposed photoresist layer having imaged and nonimaged areas to form a relief image on the substrate.
- 23. (Original) The process of Claim 22, wherein  $R_f$  and  $R_{f'}$  of the fluorine-containing copolymer are  $CF_3$ .

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- 24. (Original) The process of Claim 22, wherein the developing step is performed with an aqueous alkaline developer.
- 25. (Original) The process of Claim 22, wherein the developing step is performed with a developer selected from the group consisting of a critical fluid, a halogenated organic solvent, and a non-halogenated organic solvent.
- 26. (Original) The process of Claim 25, wherein the critical fluid is carbon dioxide.
- 27. (Original) The process of Claim 25, wherein the halogenated solvent is a fluorocarbon compound.
- 28. (Original) An article of manufacture comprising a substrate coated with a photoresist composition of Claim 19.

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